



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Akira SHIMOKOHBE et al.

Application No.: 09/556,795

Filed: April 25, 2000

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Group Art Unit: 2829

Examiner:

Asok K. Sarkar 2

Docket No.:

106096

A THIN FILM-STRUCTURE AND A METHOD FOR PRODUCING THE SAME

AMENDMENT UNDER 37 C.F.R. §1.111

Director of the U.S. Patent and Trademark Office Washington, D.C. 20231

Sir:

For:

In reply to the Office Action mailed March 22, 2002, please amend the aboveidentified application as follows:

IN THE CLAIMS:

Please replace claim 3 as follows:

3. (Three Times Amended) A method for producing a thin film-structure comprising the steps of:

forming on a substrate a thin film made of an amorphous material film exhibiting a viscous flow within a range of 10^8 - 10^{13} Pa·S when heated at a temperature within a supercooled liquid phase region;

heating the thin film to a temperature within the supercooled liquid phase

deforming the thin film to a given shape without the use of an external force;

and

region;